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Docket No.: 5199/Consilium/MBE

PATENT/OFFICIAL

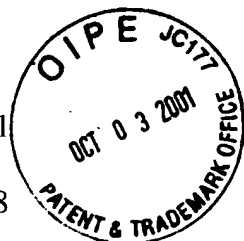
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Yueshian T. CHI et al

Serial No. 09/725,908

Filed: November 30, 2000



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Group Art Unit: 2152
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Examiner:

For: DYNAMIC SUBJECT INFORMATION GENERATION IN MESSAGE SERVICES OF
DISTRIBUTED OBJECT SYSTEMS

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D. C. 20231

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Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

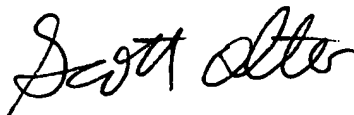
This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott Alter", written in a cursive style.

Scott M. Alter

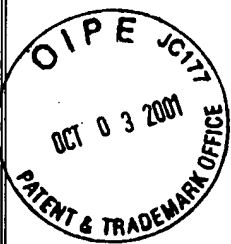
Registration No. 32,879

1455 Pennsylvania Avenue, NW
Washington, DC 20004

TEL 202.942.8428 SMA:lrr

FAX 202.942.8484

Date: 10/3/01

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 5199/Consilium/MBE		SERIAL NO. 09/725,908	
				APPLICANT Yuehshian T. CHI et al.			
				FILING DATE November 30, 2000		GROUP 2152	

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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	4,796,194	01/03/89	Atherton			08/20/86
	5,089,970	02/18/92	Lee et al.			10/05/89
	5,108,570	04/28/92	Wang			03/30/90
	5,236,868	08/17/93	Nulman			04/20/90
	5,260,868	11/09/93	Gupta et al.			10/15/91
	5,295,242	03/15/94	Mashruwala et al.			11/02/90
	5,309,221	05/03/94	Fischer et al.			12/31/91
	5,367,624	11/22/94	Cooper			06/11/93
	5,398,336	03/14/95	Tantry et al.			06/16/93
	5,402,367	03/28/95	Sullivan et al.			07/19/93
	5,408,405	04/18/95	Mozumder et al.			09/20/93
	5,410,473	04/25/95	Kaneko et al.			12/16/92
	5,490,097	02/06/96	Swenson et al.			08/06/93
	5,629,216	05/13/97	Wijaranakula et al.			02/27/96

FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	HEI 1-283934	11/15/89	Japan			X	
	HEI 8-149583	06/07/96	Japan			X	
	HEI 9-34535	02/07/97	Japan			X	
	EP 0877308	11/11/98	Europe			X	
	HEI 11-67853	03/09/99	Japan			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	
	Dishon, G., D. Eylon, M. Finarov, and A. Shulman. "Dielectric CMP Advanced Process Control Based on Integrated Monitoring." Ltd. Rehoveth, Israel: Nova Measuring Instruments.
	Runyan, W. R., and K. E. Bean. 1990. "Semiconductor Integrated Circuit Processing Technology." pg. 48. Reading, Massachusetts: Addison-Wesley Publishing Company.

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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				APPLICANT Yuehshian T. CHI et al.			
				FILING DATE November 30, 2000		GROUP 2152	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	5,661,669	08/26/97	Mozumder et al.			06/07/95	
	5,698,989	12/16/97	Nulman			09/13/96	
	5,719,495	02/17/98	Moslehi			06/05/96	
	5,740,429	04/14/98	Wang et al.			07/07/95	
	5,751,582	05/12/98	Saxena et al.			09/24/96	
	5,754,297	05/19/98	Nulman			04/14/97	
	5,764,543	06/09/98	Kennedy			06/16/95	
	5,808,303	09/15/98	Schlagheck et al.			01/29/97	
	5,883,437	03/16/99	Maruyama et al.			12/28/95	
	5,910,011	06/08/99	Cruse			05/12/97	
	6,054,379	04/25/00	Yau et al.			02/11/98	
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	Zorich, Robert. 1991. <i>Handbook of Quality Integrated Circuit Manufacturing</i> . pp. 464-498 San Diego, California: Academic Press, Inc.						
	Rampalli, Prasad, Arakere Ramesh, and Nimish Shah. 1991. CEPT—A Computer-Aided Manufacturing Application for Managing Equipment Reliability and Availability in the Semiconductor Industry. New York, New York: IEEE.						
	Moyne, James R., Nauman Chaudhry, and Roland Telfeyan. 1995. "Adaptive Extensions to a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . Ann Arbor, Michigan: University of Michigan Display Technology Manufacturing Center.						
	Moyne, James, Roland Telfeyan, Arnon Hurwitz, and John Taylor. August 1995. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Advanced Semiconductor Manufacturing Conference and Workshop</i> . Ann Arbor, Michigan: The University of Michigan, Electrical Engineering & Computer Science Center for Display Technology & Manufacturing.						
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U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB-CLASS
	09/363,966	07/29/99	Arackaparambil et al.	Computer Integrated Manufacturing Techniques		
	09/469,227	12/22/99	Somekh et al.	Multi-Tool Control System, Method and Medium		
	09/619,044	07/19/00	Yuan	System and Method of Exporting or Importing Object Data in a Manufacturing Execution System		
	09/637,620	08/11/00	Chi et al.	Generic Interface Builder		
	09/656,031	09/06/00	Chi et al.	Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers		

FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB-CLASS	Translation
						Yes No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	
	Dishon, G., M. Finarov, R. Kipper, J.W. Curry, T. Schraub, D. Trojan, 4 th Stambaugh, Y. Li and J. Ben-Jacob. February 1996. "On-Line Integrated Metrology for CMP Processing." Santa Clara, California: VMIC Speciality Conferences, 1 st International CMP Planarization Conference.
	SEMI. [1986] 1996. "Standard for Definition and Measurement of Equipment Reliability, Availability, and Maintainability (RAM)." SEMI E10-96.
	Van Zant, Peter. 1997. <i>Microchip Fabrication: A Practical Guide to Semiconductor Processing</i> . Third Edition, pp. 472-478. New York, New York: McGraw-Hill.
	Campbell, W. Jarrett, and Anthony J. Toprac. February 11-12, 1998. "Run-to-Run Control in Microelectronics Manufacturing." Advanced Micro Devices, TWMCC.
	Consilium. August 1998. <i>Quality Management Component: QMC™ and QMC-Link™ Overview</i> . Mountain View, California: Consilium, Inc.
	Consilium. 1998. <i>FAB300™</i> . Mountain View, California: Consilium, Inc.
	Khan, Kareemullah, Victor Solakhain, Anthony Ricci, Tier Gu, and James Moyne. 1998. "Run-to-Run Control of ITO Deposition Process." Ann Arbor, Michigan.
	Moyne, James and John Curry. June 1998. "A Fully Automated Chemical-Mechanical Planarization Process."

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U.S. PATENT DOCUMENTS									
EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE		CLASS	SUB- CLASS		
	09/655,542	09/06/00	Yuan	System, Method and Medium for Defining Palettes to Transform an Application Program Interface for a Service					
FOREIGN PATENT DOCUMENTS									
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS		SUB- CLASS	Translation <table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td>Yes</td> <td>No</td> </tr> </table>	Yes	No
Yes	No								
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
	SEMI. July 1998. <i>New Standard: Provisional Specification for CIM Framework Domain Architecture</i> . Mountain View, California: SEMI Standards. SEMI Draft Doc. 2817.								
	Consilium. July 1999. "Increasing Overall Equipment Effectiveness (OEE) in Fab Manufacturing by Implementing Consilium's Next-Generation Manufacturing Execution System - MES II." Semiconductor Fabtech Edition 10.								
	Consilium Corporate Brochure. October 1999. www.consilium.com								
	Consilium. January 1999. "FAB300™: Consilium's Next Generation MES Solution of Software and Services which Control and Automate Real-Time FAB Operations." www.consilium.com/products/fab300_page.htm#FAB300 Introduction								
	Consilium. November 1999. <i>FAB300™ Update</i> .								
	SEMI. 2000. "Provisional Specification for CIM Framework Scheduling Component." San Jose, California. SEMI E105-1000.								
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